

Figure 1. Synthesis of EtCpIn using the modification of the procedure for CpIn\*  
 \* O. T. Beachley, et. al., Organometallics, 7 (5), 1051–1059 (1988)

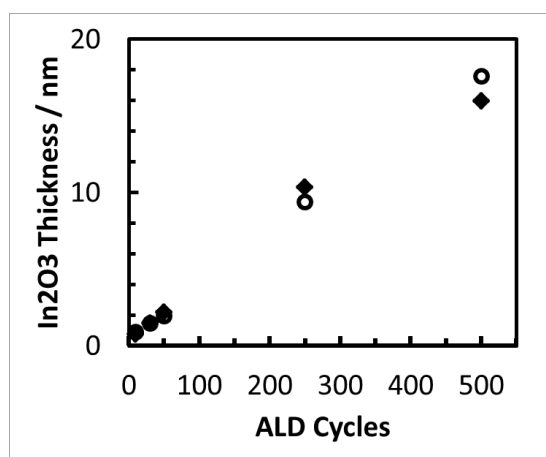


Figure 2. Film thickness vs. number of ALD cycles for films deposited by *WpO process* (◆) and *pO process* (○).

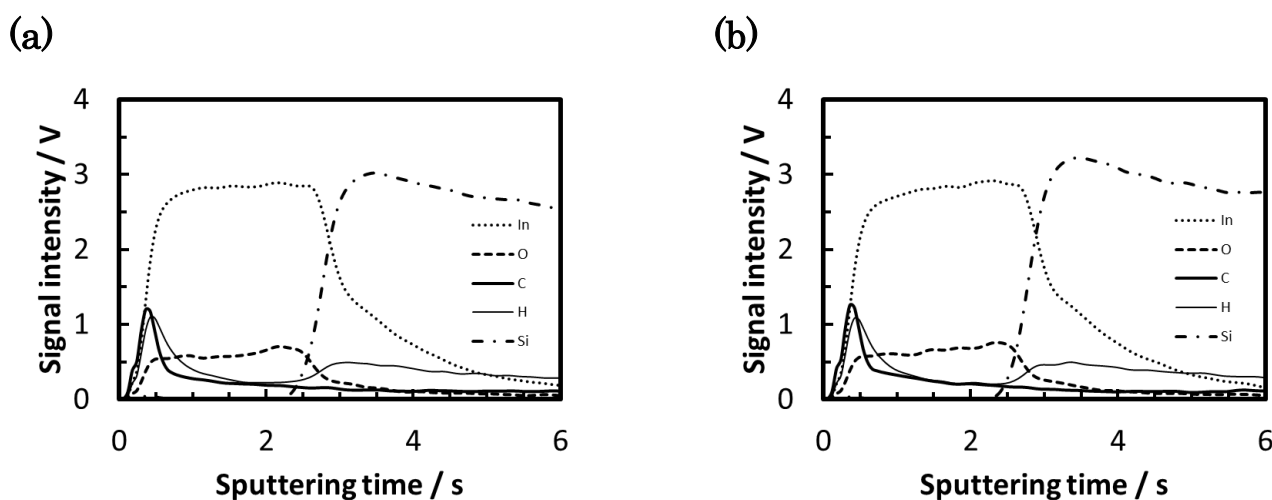


Figure 3. Rf-GDOES depth profiles of indium oxide films deposited to 500 cycles by WpO process (a) and by pO process (b).